

Large Area Nanogratings

- 1 D
- rectangular
- hexagonal

Application:

- Master for Imprint Templates
- Microoptics
- NanoBio Technology
- Measurement

AMO offers gratings fabricated by inhouse interference lithography (IL). The IL technology allows producing large, coherent and periodic gratings with nearly constant pitch. Pattern transfer and further processing can be carried out according to customer requirements. Substrates up to 6 inch and any rectangular within.

Process Control:

All grating dimensions are specified and controlled during and after processing. Line width maps, LER characterisation and defect inspection are available on request.

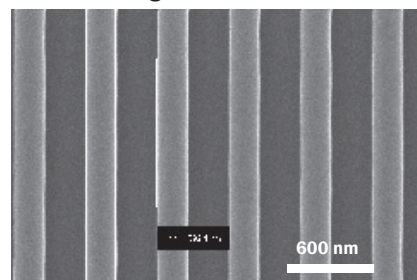
Specification:

Substrate material	Silicon or fused silica
Substrate thickness	Typical 500 μm to 650 μm
Substrate size	Up to 6 inch and any rectangular within.
Grating pitch	180 nm to 2500 nm
Etch depth	90 nm to 2500 nm
Line width	40 nm to 1500 nm
Active grating area	Up to 140 mm in diameter

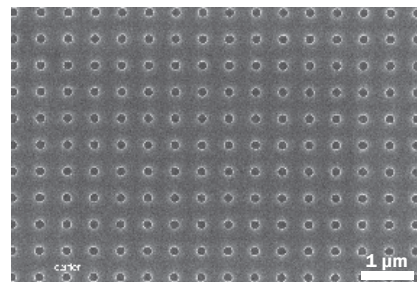
Some specifications are matter of negotiation. For further details please contact us.

- Contact: Dipl.-Ing. Michael Möller ■ moeller@amo.de

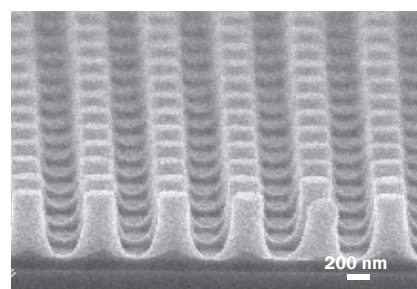
Linear Gratings



Hole Pattern



Pillar Pattern



AMO GmbH

Otto-Blumenthal-Straße 25 ■ D-52074 Aachen ■ Germany
 Phone +49 241 88 67-200 ■ Fax +49 241 88 67-560
 info@amo.de ■ www.amo.de